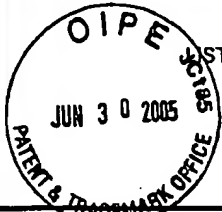
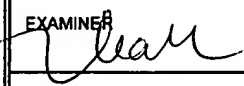


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1518		SERIAL NO. 09/653,156	
				LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			
				APPLICANT: Vishnu K. Agarwal et al.			
				FILING DATE August 31, 2000		GROUP 2813	
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	AL						
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TN	AM	Ritala et al.; <i>Perfectly Conformal TiN and Al2O3 Films Deposited by Atomic Layer Deposition</i> ; Chemical Vapor Deposition, v. 5, No. 1, 1999, pp. 7-9.					
	AN						
	AO						
EXAMINER 		DATE CONSIDERED 8/30/05					
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